

**METHOD AND APPARATUS FOR ADJUSTING THE THICKNESS OF A  
LAYER OF SEMICONDUCTOR MATERIAL**

**ABSTRACT**

5           A method for adjusting the thickness of a thin  
semiconductor material layer. The technique includes  
measuring the layer to establish a thickness profile,  
comparing the measured thickness profile with stored  
standard profiles, wherein each standard profile is  
10   stored in association with respective thickness  
adjustment specifications, selecting a stored standard  
profile to associate the layer with the respective  
thickness adjustment specification, and adjusting the  
thickness of the layer in accordance with the thickness  
15   adjustment specification. The invention also provides  
apparatus for adjusting the thickness of a thin  
semiconductor material layer.